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| Session Title: | [WeF2] Nano Thin Film Deposition IV |
| Session Date: | November 13 (Wed.), 2024 |
| Session Time: | 14:10-15:55 |
| Session Room: | Room F (Ballroom, 5F, Grand Josun Busan) |
| Session Chair: | Dr. Mihaela Popovici (imec, Belgium) |

[WeF2-1] [Invited]

14:10-14:40

Nano Thin Film Technologies for Charge Trap Flash in VNAND

HanMei Choi, Bio Kim, HyungJoon Kim, Kwangmin Park, Philouk Nam, Kyong-Won An, DongHun Sin, Guk-Hyon Yon, Jaehyun Yang, Dongsung Choi, Sangsoo Lee, Sookyem Yong, Heedon Hwang, JongMyeong Lee (Samsung Electronics Co., Ltd., Korea)

[WeF2-2] [Invited]

14:40-15:05

SMART Nanometallization for Energy-Efficient and Reliable Edges

Hanwool Yeon (GIST, Korea)

[WeF2-3] [Invited]

15:05-15:30

Recent Advances in Mo-Based Electrode Materials for High-Performance DRAM Cell Capacitors

Jeong Hwan Han (Seoul Nat'l Univ. of Science and Tech., Korea)

[WeF2-4] [Invited]

15:30-15:55

Advanced ALD Process for Meta-Stable Phased Thin Film Deposition

Woojin Jeon (Kyung Hee Univ., Korea)